# Opportunities in vertexing and tracking

Jens Dopke, Laura Gonella UK meeting on future e+e- Higgs/EW/top/... Factory Oxford, 5 July 2022

### Outline

- Tracking and vertex requirements for future e+e- colliders
- Existing detector concepts
- Technology roadmap
- Discussion on opportunities for the UK

### Future e<sup>+</sup>e<sup>-</sup> colliders



### Requirements for Vertex and Tracking Detectors

"Technical" Start Date of Facility (This means, where the dates are not known, the earliest technically feasible start date is indicated - such that detector R&D readiness is not the delaying factor)			< 2030			2030-2035				2035 - 2040 2040-2045		> 2045							
			Panda 2025	CBM 2025	NA62/Klever 2025	Belle II 2026	ALICE LS3 <sup>11</sup>	ALICE 3	LHCb (≳LS4) <sup>1)</sup>	ATLAS/CMS (≳ LS4) <sup>1)</sup>	EIC	LHeC	11C <sup>2)</sup>	FCC-ee	CLIC <sup>2)</sup>	FCC-hh	FCC-eh	Muon Collider	
			Position precision σ <sub>hit</sub> (μm)		≃5		≲5	۲ ۲	≲3	≲10	≲15	≲3	≃ 5	≲3	≲3	≲3	≃7	≃ 5	≲5
		4 17	X/X <sub>0</sub> (%/layer)	≲0.1	<b>≃</b> 0.5	<b>≃</b> 0.5	≲0.1	≃ 0.05	≃ 0.05	≃1		≃ 0.05	≲0.1	≃ 0.05	≃ 0.05	≲0.2	≃1	≲0.1	≲0.2
۳L	cmos	RDT 3. RDT 3.	Power (mW/cm²)		≃ 60			<b>≃</b> 20	≃ 20			≃ 20		<b>≃</b> 20	≃ 20	≃ 50			
etector	vPS assive ADs		Rates (GHz/cm <sup>2</sup> )		≃0.1	≃1	≲0.1		≲0.1	≃6		≲0.1	<b>≃</b> 0.1	<b>≃</b> 0.05	≃ 0.05	≃5	<b>≃</b> 30	≃0.1	
ertex D	MA -/3D/P LG		Wafers area (") <sup>4)</sup>					12	12			12			12		12		12
ž	Planar	DRDT 3.2	Timing precision $\sigma_t (ns)^{5}$	10		≲0.05	100		25	≲ 0.05	≲0.05	25	25	500	25	≃5	≲0.02	25	≲0.02
		DRDT3.3	Radiation tolerance NIEL (x 10 <sup>16</sup> neg/cm <sup>2</sup> )							≃6	≃ 2						$\simeq 10^2$		
			Radiation tolerance TID (Grad)							≃1	<b>≃</b> 0.5						<b>≃ 30</b>		
			Position precision σ <sub>hit</sub> (μm)						≃6	≃5		≃6	≃6	≃6	≃6	≃7	≃ <b>10</b>	≃6	
			X/X <sub>0</sub> (%/layer)						≃1	≃1		≃1	≃1	≃1	≃1	≃1	≲2	≃1	
	SMOS	RDT3. RDT3.	Power (mW/cm²)						≲100	≃ 100		≲100		≲100	≲100	≲150			
Tracker <sup>6)</sup> MAPS	PS assive ( ADs	00	Rates (GHz/cm <sup>2</sup> )							≃ 0.16									
	/3D/P. /G/P.		Wafers area (") <sup>4)</sup>						12			12		12	12	12	12		12
	Planar	DRDT 3.2	Timing precision $\sigma_t (ns)^{5)}$						25	≲ 25		25	25	≲0.1	≲0.1	≲0.1	≲0.02	25	≲0.02
		I3.3	Radiation tolerance NIEL (x 10 <sup>16</sup> neg/cm <sup>2</sup> )							≃0.3							≲1		
		DRD	Radiation tolerance TID (Grad)							≃ 0.25							≲1		

https://cds.cern.ch/record/2784893







#### **ILC concepts**





#### **FCC-ee concepts**



- Large-volume solenoid, enclosing calorimeters and tracking.
  - Only exception IDEA concept.
  - Smaller B-field, larger tracker outer radius at FCC-ee to retain momentum resolution.
- · Highest precision, lowest mass, smaller radius vertex detector.
  - Silicon pixel detectors (MAPS, hybrids).

	ILD	SiD	CLICdet	CLD	IDEA	CEPC
Vertex technology	Si	Si	Si	Si	Si	Si
Vertex inner radius [cm]	1.6	1.4	3.1	1.75	1.7	1.6
Tracker technology	TPC + Si	Si	Si	Si	Drift chamber + Si	Si
Tracker outer radius [m]	1.77/1.43	1.22	1.5	2.1	2.0	1.8
Calorimeter	PFA	PFA	PFA	PFA	Dual readout	PFA
Solenoid field [T]	3.5/4	5	4	2	2	3
Solenoid length [m]	7.9	6.1	8.3	7.4	6.0	8.0
Solenoid inner radius [m]	3.42/3.08	2.6	3.5	3.7	2.1	3.4

- Large area, low mass tracking detector.
  - Cost and ease of construction are key drivers for technological development.
  - All silicon (pixel/strip detectors) or silicon + gaseous detectors (TPC, drift chamber).
  - Gas detectors provide low mass, low cost large lever arm coverage with added PID.

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- Bunch trains (linear) vs. continuous beam (circular).
  - Power pulsing of FE electronics at linear colliders, no need for active cooling (i.e. air cooling can be used) → reduced material.
  - Bunch spacing down to 20 ns at FCC-ee, active cooling required → challenging to meet power management within low mass requirements, cooling studies for low mass, new technology nodes for low power electronics.



- Beam-induced backgrounds more challenging at linear colliders.
  - CLIC 3TeV worse case: largest vertex detector inner radius; up to 8.8 hits/mm<sup>2</sup>/train; 0.5 ns bunch spacing results in out-of-time pile-up, ns-level timing needed.
- Extremely high luminosities at FCC-ee (Z pole).
  - High statistical precision requires control of systematics down to 10<sup>-5</sup> level → significant implications for the design of a stable and lightweight mechanical support.

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### Technology development

- The existing vertex and tracking detector concepts are based on R&D prototype technologies (or extrapolations from state-of-the-art detectors).
- Many years of development of detector technologies for e+e- colliders provide solutions that meet some but not all key requirements.
- R&D (following the ECFA roadmap) is needed to meet all requirements and to further improve performance.

#### For solid state detectors:

#### DRDT 3.1 - Achieve full integration of sensing and microelectronics in monolithic CMOS pixel sensors.

Developments of Monolithic Active Pixel Sensors (MAPS) should achieve very high spatial resolution and very low mass, aiming to also perform in high fluence environments. To achieve low mass in vertex and tracking detectors, thin and large area sensors will be crucial. For tracking and calorimetry applications MAPS arrays of very large areas, but reduced granularity, are required for which cost and power aspects are critical R&D drivers. Passive CMOS designs are to be explored, as a complement to standard sensors fabricated in dedicated clean room facilities, towards hybrid detector modules where the sensors is bonded to an independent ASIC circuit. Passive CMOS sensors are good candidates for calorimetry applications where position precision and lightness are not major constraints (see Chapter 6). State-of-the-art commercial CMOS imaging sensor (CIS) technology should be explored for suitability in tracking and vertex detectors.

### DRDT 3.2 - Develop solid state sensors with 4D-capabilities for tracking and calorimetry.

Understanding of the ultimate limit of precision timing in sensors, with and without internal multiplication, requires extensive research together with the developments to increase radiation tolerance and achieve 100%-fill factors. New semiconductor and technology processes with faster signal development and low noise readout properties should also be investigated.

#### https://cds.cern.ch/record/2784893

DRDT 3.3 - Extend capabilities of solid state sensors to operate at extreme fluences.

To evolve the design of solid state sensors to correct the properties of silicon and the properties of silicon and the sensors in the fluence range  $1 \times 10^{16} n_{eq} \text{ cm}^{-2}$  to  $5 \times 10^{18} n_{eq} \text{ cm}^{-2}$  and to the sensors in the fluence range adlation models which correspondingly include results from microscopic to the sensor of point and cluster defects. All technologies will need improved radia to the sensor of the defect of the sensor of the sensor of the sensor of the defect of the sensor of the sensor of the defect. As specific concern to be addressed is the associated activation of all the sensor of the defect. Exploration is desirable on alternative semiconductors and 2 to the sensor of the sensor o

#### DRDT 3.4 - Develop full 3D-interconnection technologies for solid state devices in particle physics.

3D-interconnection is commercially used, for instance in imaging sensors, to use the most appropriate technology process for the different functionalities of the devices. For particle physics detectors, this process would allow more compact and lighter devices with minimal power consumption. This approach also provides an alternative to the use of finer feature sizes to enable lower pitch and new digital features. An enhanced R&D effort towards building a demonstrator as a starting cornerstone is highly desirable. A demonstrator programme should be established to develop suitable silicon sensors, cost effective and reliable chip-to-wafer and/or wafer-to-wafer bonding technologies and to use these to build multi-layer prototypes with vertically stacking layers of electronics, interconnected by through-silicon vias (TSVs) and integrating silicon photonics capabilities.



### Technology impact on physics programme

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	DRDT		< 2030	2030-2035	2035- 2040 2040	4 >2045
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Low power	3.1,3.4		🔹 🤞 🍎 🍎	🍎 🍝 🍝 🍎 🌢	ÓÓÓ	<b>Ö o Ö</b>
High rates	3.1,3.4		• • •	<b>•</b> • • •	) i i i	<b>Ö O</b>
Large area wafers <sup>3)</sup>	3.1,3.4		🔶 🍈 🔶 🔴			•
Ultrafast timing <sup>4)</sup>	3.2					• •
Radiation tolerance NIEL	3.3					
Radiation tolerance TID	3.3			• •		
Position precision	3.1,3.4			•••		
Low X/X <sub>o</sub>	3.1,3.4					
Low power	3.1,3.4					
High rates	3.1,3.4					
Large area wafers <sup>3)</sup>	3.1,3.4					• • •
Ultrafast timing <sup>4)</sup>	3.2					
Radiation tolerance NIEL	3.3			•		
Radiation tolerance TID	3.3					
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The colour coding is linked not to the is irred effort but to the potential impact on the physics programme of ust happen or main physics goals cannot be met (red, largest dot) t several physics goals (orange, large dot); Desirable to enhance phedium dot); R&D needs being met (green, small dot); No further I applicable (blank). <b>https://cds.cern.ch/record/2784893</b> <b>DRDT</b> Position precision 3.1,3.4 Low X/X <sub>0</sub> 3.1,3.4 Low power 3.1,3.4 High rates 3.1,3.4 Ultrafast timing <sup>4</sup> 3.2 Radiation tolerance NIEL 3.3 Radiation tolerance TID 3.3 Position precision 3.1,3.4 Low X/X <sub>0</sub> 3.1,3.4 Low X/X <sub>0</sub> 3.1,3.4 Ultrafast timing <sup>4</sup> 3.2 Radiation tolerance NIEL 3.3 Radiation tolerance TID 3.1 Position precision 3.1,3.4 Low X/X <sub>0</sub> 3.1,3.4 Ultrafast timing <sup>4</sup> 3.2 Radiation tolerance NIEL 3.3 Radiation tolerance TID 3.3 Position precision 3.1,3.4 Low X/X <sub>0</sub> 3.1,3.4 Low for the precision 3.1,3.4 Radiation tolerance TID 3.3 Position precision 3.1,3.4 Low for the precision 3.1,3.4 Radiation tolerance NIEL 3.3 Radiation tolerance TID 3.3	ematic timeline of categories of experiments employing solid state sensors DRDTs and R&D tasks. 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on collide.

### Emerging/future technologies

k lice LS3     Belle II CBM     NA62     LHCb, ATLAS, CMS ( $\gtrsim$ LS4) <sup>3</sup> ALICE 3 - EIC     ILC     FCC-ee     CLIC     FCC-hh       k     technology node <sup>3</sup> $65 \text{ nm}$ - stitching $65 \text{ nm}$ - stitching     c     c $28 \text{ m}$ $328 \text{ m}$ $28 \text{ m}$	Muon Collider ≲28 nm
technology node <sup>11</sup> $\frac{65 \text{ nm}}{\text{stitching}}$ $65 \text{ nm} - \text{stitching}$ $28 \text{ nm}$ $\lesssim 28 \text{ nm}$ $\simeq 10 \text{ nm}$ pitch     10 - 20 \mum     10 - 20 \mum     10 - 20 \mum     10 - 20 \mum $\simeq 10 \text{ nm}$ $\gamma$ $10 - 20 \mu$ 10 - 20 \mum $\sim 10 \text{ nm}$ $\sim 10 \text{ nm}$ $\gamma$ $10 - 20 \mu$ $10 - 20 \mu$ $\sim 10 \text{ nm}$ $\sim 10 \text{ nm}$ $\gamma$	≲ 28 nm
μ         10 - 20 μm         10 - 20 μm         pitch ≤ 10 μm for q <sub>m</sub> ≤ 3 μm in VD           2         wafer size <sup>20</sup> 12"         Reduce z-granularity in TK - pad granularity in analog Cal.	
Pitch         Reduce z-granularity in TK - pad granularity in analog Cal.           2         water size <sup>21</sup> 12"         12"	
2 water cira <sup>3</sup> 12" 12" 12" 12"	
2 rate <sup>31</sup> O(100) MHz/cm <sup>2</sup> 5 GHz/cm <sup>2</sup> 30 GHz/cm <sup>2</sup>	
ultrafast timing <sup>4)</sup> 0,520 ps 0,520 ps	
radiation tolerance 3 x 10 <sup>15</sup> neq/cm <sup>2</sup> 10 <sup>18(16)</sup> neq/cm <sup>2</sup> VD/CaL(Trk)	
technology node <sup>1)</sup> (SOLCUP ASIC 28 nm ASIC ≤ 28 nm ASIC ≤ 28 nm ASIC ≤ 28 nm	ASIC ≲ 28 nm
δ ≤ 25 μm in VD ≤ 10 μm for q <sub>it</sub> ≤ 3 μm in VD	
0 pitch ≤ 50 μm for q <sub>tt</sub> ≤ 10 μm in Trk	
22 wafer size <sup>2)</sup> 12"	
G rate <sup>31</sup> 6 GHz /cm <sup>2</sup> 30 GHz/cm <sup>2</sup>	
d ultrafast timing <sup>4</sup> σt ≈ 50 - 100 ps σt ≲ 100 ps σt ≲ 100 ps σt ≤ 20 ps	
radiation tolerance 6 x 10 <sup>16</sup> neq/cm <sup>2</sup>	
technology node <sup>10</sup> COLICIE ASIC ≥ 28 nm ASIC ≥ 28 nm ASIC ≥ 10 nm	
pitch $\approx 300 \mu m$ (100% fill facor) same as for other technologies with ultimate pitch $\lesssim 10 \mu m$ for $\sigma_{it} \lesssim 3 \mu m$ in (100% fill facor)	۱VD
ර wafer size <sup>2)</sup> > 3" 12"	
6 GHz /cm <sup>2</sup> 30 GHz/cm <sup>2</sup>	
ultrafast timing <sup>4</sup> $\sigma_t \leq 30 \text{ ps} \qquad \sigma_t \leq 20 \text{ ps} \text{ (PID)} \qquad \sigma_t = 20 \text{ ps} $	rk/Cal.
radiation tolerance $\geq 5 \times 10^{15} \text{ neg/cm}^2$ $\frac{10^{18(10)} \text{ neg/cm}^2}{\text{VD/Cal.(Trk)}}$	
sensor thickness <sup>51</sup> < 50 μm MAPS / Plan/3D/Pass. < 50 μm MAPS, Planar/3D/Passive CMOS, LGADs	
ਨੂੰ ਹੈ < 50 µm LGADs	

Figure 3.3: Compilation of the technology R&D needs and timeline for future solid state The colour coding is linked not to the intensity of the required effort but indicates what key progress would be need for a technology to enter a project (red), (green) when it would be desirable (yellow), or when it is being met detectors.

Smaller feature size technologies to further improve granularity, power consumption, rate, radiation hardness, ...



### Silicon detector technologies



- Sensor optimisation (3D, LGAD, passive CMOS, ...)

 $-65 \rightarrow 28 \text{ nm ASICs}$ 

 New interconnection technologies (fine pitch bump-bonding, ACF, ...)

SOI, 3D integration, capacitively coupled devices.

Improved charge collection via full depletion (HV/HR-CMOS), driven by high rate, high radiation experiments.
Higher granularity, lower mass with smaller feature size CMOS.

<u>SiGe BiCMOS, SPAD</u>: Ultimate timing.

<u>CCD</u> (various types): Ultimate pixel size.

### DRDT 3.1 - Monolithic CMOS

- Monolithic Active Pixel Sensors (MAPS) in commercial CMOS imaging technology could provide solutions for both vertex and tracking layers at e+e- colliders.
  - High granularity and low power consumption demonstrated by state-of-the art, further improved by the use of smaller technology nodes (see next slide).
  - Low cost, large volume production and ease of assembly would favour use in trackers wrt. strips.
    - Tracking detectors is an area where there is a lot of UK expertise.
    - Also consider overlapping requirements with calorimeters, and UK work on that  $\rightarrow$  possible synergies?

#### ALPIDE @ ALICE ITS2 Example state-of-the-art MAPS detector



10m<sup>2</sup> surface Inner Barrel = 0.3% X/X0 per layer Outer Barrel = 0.8% X/X0 per layer 50 kHz interaction rate (Pb-Pb) 400 kHz interaction rate (pp)



180 nm CMOS TowerJazz 27 x 29  $\mu$ m<sup>2</sup> pixel pitch 5  $\mu$ s integration time 40 mW/cm<sup>2</sup>

### Stitched wafer scale sensors for cylindrical layers

- Exploration of 65 nm CMOS imaging processes for MAPS driven by CERN EP R&D WP1.2 and ALICE ITS3 upgrade.
  - 12" wafers, higher logic density, smaller pixels, faster read-out, lower power consumption.
- Wafer-scale, low power sensor design for truly cylindrical minimal material budget layers → New technology node & new detector concept
  - Mechanical support, power distribution and data lines outside acceptance, air cooling.
     MLR1 submission



### DRDT 3.4 - 3D integration

- Industrial developments of heterogeneous integration technologies to achieve further reductions in cost and power.
- 3D stacking is being studied for future HEP applications → potential for increased functionality and performance of silicon trackers.
- Pursuing this path would require large scale of investment and establishing a privileged relation with industrial partner(s), but it is a field where there isn't a clear leadership now.
  - Dependent on availability of process for R&D.
- There is expertise in the UK to work on each layer in the stack and on the interconnection technologies.

# Electronics (beyond sensors) (Chapter 7)

### (See Figure 7.1, R&D Roadmap for an overview)

- Under DRDT 7.2: High-granularity pixel readout chip with 10–100ps timing and charge measurement capability in 28nm CMOS, and highly programmable features
  - An opportunity to hang on to our involvement from RD53? A lot of this is chip design in IP blocks that can be useful elsewhere, but do we think it's worth the investment?
- DRDT 7.5 Evaluate and adapt to emerging electronics and data processing technologies
  - Silicon photonics as the successor to actively modulated VCSEL-based links, facilitating fullcustom photonic integrated circuits (PICs) for HEP
    - So far as I am aware this could be a wide open field with possible contributions from the UK - can significantly reduce optics power, expertise doesn't exist, but not sure it does elsewhere?
  - 3D integration and high density interconnects
    - We already have people working on some of these
- Under DRDT 7.1: Power and readout efficiency:
  - High conversion factor DC-DC converters based on new processes and materials, and associated power management circuit blocks
    - Long history of testing powering schemes, GaN HV switches fully developed through the UK now being looked at for higher efficiency DCDC at CERN

## Mechanics & cooling (Chapter 8)

(Have a look at Figure 8.1)

- DRDT 8.1 Develop novel magnet systems
- DRDT 8.2 Develop improved technologies and systems for cooling
  - Experience with microchannel cooling, but are we happy? Other approaches?
- DRDT 8.3 Adapt novel materials to achieve ultralight, stable and high precision mechanical structures. Develop Machine Detector Interfaces
  - Lots of carbon fibre experience in the UK, but lack of industry backing can be a problem
  - Work on detectors without support structures ongoing...

### Working with UK industry

- Developments that involve UK industrial partners would be beneficial for funding situation.
- Involvement of existing infrastructure for large scale assembly also to be considered (for example national labs/SRF).
- Some examples of UK company for sensor production and interconnections: Alter Technology, Custom Interconnect Ltd, ElementSix, Micron, Micross, Nordson, Te2v.
  - There is certainly more.
- We are already working with some of these industrial partners.
  - Interest from some of these companies to work with us but small-ish R&D budgets and long development cycles not attractive for their business model.

### **Opportunities for the UK - Thoughts for discussion**

- The UK community interested in e+e- colliders should identify opportunities where it can engage with the international efforts in a leading role.
- There is a large community in the UK working on many aspects of vertex and tracking detectors development, construction and operation (sensors, ASICs, mechanics, readout, cooling, DAQ, ...)  $\rightarrow$  a lot of expertise.
- At this early stage it would be good to identify technologies that are agnostic to the specific collider implementation, rather then splitting the community (and the resources) into groups working on detector R&D for different e+e- collider.
- The community should aim at a unified and coordinated vision.
  - Devise a common generic R&D programme that then can branch off for specific/targeted implementations required by different facilities.
- What we really need is a Workshop on Tracking and Vertexing for e+ecolliders, where the UK community comes together, presents their developments and identifies strengths that can culminate in a funded route for development and ultimately leadership in a section of the field.
  - What developments/expertise/links with industry can we leverage on?

### Backup

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